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Abstract

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A method of processing a substrate having an optical surface may include: providing an interferometer apparatus having an interferometer optics providing a beam of measuring light; polarizing the beam of measuring light such that a
10 tangential polarization component continuously increases relative to a radial polarization component with increasing distance from an optical axis; arranging the substrate in the beam of measuring light; interferometrically determining a surface map of the optical surface; and determining
15 deviations of the optical surface of the substrate from a target shape thereof in dependence of the surface map.

The beam of measuring light may be also polarized such that light of the beam is substantially linearly polarized in a
20 polarization direction which is substantially constant across a cross section of the beam and wherein the polarization direction is rotated about the optical axis.

(Figure 3)